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May 7, 2001

Via FEDEX

Ms. Shalini Shetty
Patent Paralegal
Technology Law Department
ADVANCED MICRO DEVICES, INC.
1160 Kern Avenue, M/S 68
Sunnyvale, CA 94088-3453

Re: New U.S. Patent Applications of Ramkumar SUBRAMANIAN et al.
Title: **TWO MASK PHOTORESIST EXPOSURE
PATTERN FOR DENSE AND ISOLATED
REGIONS**
Your Ref. F0822
Our Ref.: 039153/0381

Dear Shalini:

Enclosed please find two copies of the above captioned application that we have drafted along with the Declaration and Power of Attorney, Assignment and the Taiwanese Oath & Assignment.

Please have the inventors sign and date the forms. After the inventors have signed these forms, please forward the executed forms to us, as well as one of the two copies of the patent application, so that we can file them with the U.S. Patent and Trademark Office in the near future.

The Taiwanese Oath & Assignment enclosed herewith is for your office use and does not need to be returned to our office.

Ms. Shalini Shetty
May 7, 2001
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If the inventors have any questions and/or if they want to make any changes to the application, please call me at (202) 945-6090, and I will explain how minor changes can be made. If the changes are not-so-minor, then we will have to provide you with an updated application.

With best regards.

Very truly yours,



Leon Radomsky

LR:seh
Enclosures